

L Number	Hits	Search Text	DB	Time stamp
1	6060	438/525.ccls. 438/528.ccls. 438/586.ccls. 438/592.ccls. 438/595.ccls. 438/637.ccls. 438/675.ccls. 438/766.ccls. 438/770.ccls.	USPAT; US-PGPUB	2004/08/21 19:56
2	2658	(438/525.ccls. 438/528.ccls. 438/586.ccls. 438/592.ccls. 438/595.ccls. 438/637.ccls. 438/675.ccls. 438/766.ccls. 438/770.ccls.) and ((thermal\$4 near (process\$6 oxid\$8)) (rapid adj thermal) rto rta rtp)	USPAT; US-PGPUB	2004/08/21 20:06
3	1659	((438/525.ccls. 438/528.ccls. 438/586.ccls. 438/592.ccls. 438/595.ccls. 438/637.ccls. 438/675.ccls. 438/766.ccls. 438/770.ccls.) and ((thermal\$4 near (process\$6 oxid\$8)) (rapid adj thermal) rto rta rtp)) and (ion near implant\$8)	USPAT; US-PGPUB	2004/08/21 20:00
4	672	((((438/525.ccls. 438/528.ccls. 438/586.ccls. 438/592.ccls. 438/595.ccls. 438/637.ccls. 438/675.ccls. 438/766.ccls. 438/770.ccls.) and ((thermal\$4 near (process\$6 oxid\$8)) (rapid adj thermal) rto rta rtp)) and (ion near implant\$8)) and ((contact adj (opening hole via)) plug ((conduct\$6 metal) near via))	USPAT; US-PGPUB	2004/08/21 20:05
5	666	(((((438/525.ccls. 438/528.ccls. 438/586.ccls. 438/592.ccls. 438/595.ccls. 438/637.ccls. 438/675.ccls. 438/766.ccls. 438/770.ccls.) and ((thermal\$4 near (process\$6 oxid\$8)) (rapid adj thermal) rto rta rtp)) and (ion near implant\$8)) and ((contact adj (opening hole via)) plug ((conduct\$6 metal) near via))) and (gate source drain sidewall spacer silicide (side adj wall))	USPAT; US-PGPUB	2004/08/21 20:04
7	371	((thermal\$4 near (process\$6 oxid\$8)) (rapid adj thermal) rto rta rtp) same (ion near implant\$8) same ((contact adj (opening hole via)) plug ((conduct\$6 metal) near via)) same (gate source drain sidewall spacer silicide (side adj wall))	USPAT; US-PGPUB	2004/08/21 20:08
9	152	((thermal\$4 near (process\$6 oxid\$8)) (rapid adj thermal) rto rta rtp) same (ion near implant\$8) same ((contact adj (opening hole via)) plug ((conduct\$6 metal) near via)) same (gate source drain) same (sidewall spacer silicide (side adj wall))	USPAT; US-PGPUB	2004/08/21 20:09
6	152	((((438/525.ccls. 438/528.ccls. 438/586.ccls. 438/592.ccls. 438/595.ccls. 438/637.ccls. 438/675.ccls. 438/766.ccls. 438/770.ccls.) and ((thermal\$4 near (process\$6 oxid\$8)) (rapid adj thermal) rto rta rtp)) and (ion near implant\$8)) and (sac (aligned adj contact))	USPAT; US-PGPUB	2004/08/21 20:45
11	1	20020079492.pn.	USPAT; US-PGPUB	2004/08/21 20:45
12	13	("4753896" "5518946" "5731236" "5817562" "5930634" "6083816" "6123766" "6160271" "6187676" "6200840" "6258675" "6350665" "6436818" "2002/0001935" "2002/0084482").PN.	USPAT	2004/08/21 20:46
13	0	6649500.URPN.	USPAT	2004/08/21 20:48
14	2	6268272.URPN.	USPAT	2004/08/21 20:48
15	9	("4443930" "4450620" "5510295" "5541131" "5607884" "5731239" "5759899" "5869397" "5924001").PN.	USPAT	2004/08/21 20:49
16	0	6255206.URPN.	USPAT	2004/08/21 20:50
17	12	("5012320" "5023682" "5130266" "5268321" "5320975" "5648287" "5672544" "5741725" "5874353" "5880500" "5994192" "6001718").PN.	USPAT	2004/08/21 20:50
10	167	((thermal\$4 near (process\$6 oxid\$8)) (rapid adj thermal) rto rta rtp) same (ion near implant\$8) same ((contact adj (opening hole via)) plug ((conduct\$6 metal) near via) sac (aligned adj contact)) same (gate source drain) same (sidewall spacer silicide (side adj wall))	USPAT; US-PGPUB	2004/08/21 20:52
8	205	((thermal\$4 near (process\$6 oxid\$8)) (rapid adj thermal) rto rta rtp) and (ion near implant\$8) and ((contact adj (opening hole via)) plug ((conduct\$6 metal) near via)) and (gate source drain sidewall spacer silicide (side adj wall))	EPO; JPO; DERWENT; IBM_TDB	2004/08/21 21:26